

Dual Chamber Electron Beam Evaporation System

Model: SA-VKE800D

SA-VKE800D is a multi-purpose electron beam evaporation platform built for universal application. It combines outstanding performance, consistent stable running, full automatic control and low maintenance costs, fully accommodating varied e-beam evaporation workflows in industrial manufacturing and academic R&D.



Feature

- Low cost
- Lift-off
- Co-deposition
- High evaporation rate

Application

- Laser
- R&D
- Integrated circuit
- MEMS

Specifications:

Parameter	Descriptions
Number of Crucibles	6(max.)
Automatic Loadlocks	Single & multi-chip automatic loadlock
Workpiece Angle	-45°~45°, adjustable
Power Supply	10kW(max.)
Film thickness monitoring	Crystal oscillator controller
Ion Source	Kaufman & Hall ion source
Fixture types	Dome & Planetary
Pumping System	Cryopump / magnetically levitated turbo-molecular pump + Dry mechanical pump
Coating Uniformity	±2%
Coating Repeatability	±2%
Uniform Deposition Area	Ø300 mm(max.)
Ultimate Vacuum	1E-5Pa
Vacuum Measurement	Full-range vacuum gauge
Temperature Control Range	RT~500℃
Space Requirements(L×W×H,m)	4.0×3.1×2.9

Principle:

